

REMARKS

Claims 3-7, 15-17, 51 and 215-218 are pending in the application.

Claim 3 is amended to recite that the first insulating interlayer comprises at least one material chosen from of a SiO₂ layer and a low-k material layer, and that if a low k-material is chosen, the material comprises one of a SiOF layer, a SiOC layer, a ladder-type hydrogen siloxane layer and a porous ladder-type hydrogen siloxane layer. Support for the amendments can be found in the present specification, for example, at page 19, lines 3-9 and page 24, lines 20-25.

Claim 16 is amended to clearly define the silicon-diffused metal layer. Support for the amendment can be found, for example, at claim 3.

Claim 17 is amended to recite that the component of the etching stopper layer, with support in the present specification at page 15, lines 31-33.

Claim 51 is amended it delete an extra “and” at line 7.

Claim 218 is amended to provide antecedent basis for the phrase “said first etching stopper layer”, and to define the etching stopper layer. Support for the amendment can be found, for example, at claim 217 and at page 14, lines 31-33.

Claims 215-218 are amended to delete the recitation of “including no carbon therein” from the claim language.

The present amendments to the claims are made only to overcome § 112 rejections with support in the specification. Accordingly, it is believed that no new consideration or search is required, and thus, entry of the Amendment after a Final Office Action is respectfully requested.

Response to Claim Rejections Under 35 U.S.C. § 112

Claims 3-7, 15-17, 51 and 215-218 are rejected under 35 U.S.C. § 112, second paragraph, as allegedly being indefinite.

Initially, Applicants submit that claims 3, 16, 51 and 218 are amended to overcome the §112, second paragraph rejection.

Additionally, the Examiner asserts that independent claims 3, 15-17 and 215-218 recite a "first insulating interlayer", "first metal-diffusion barrier layer", "first etching stopper", and "a copper-diffused copper layer", and all of the above layers comprises at least one of a SiCN layer, a SiC layer, a SiOC layer. Therefore, it is the Examiner's position that it is confusing that these different layers can be defined differently, but have the same components

Applicants respectfully submit that the present claims are amended to recite different materials for the insulating interlayer, copper-diffusion barrier layer, metal-diffusion barrier layer and the etching stopper layer, thereby overcoming the § 112 rejection of the claims.

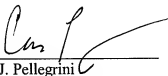
In view of the above, Applicants respectfully submit that all pending claims are in condition for allowance. Therefore, reconsideration and withdrawal of the § 112 rejections are respectfully requested.

Conclusion

In view of the above, reconsideration and allowance of this application are now believed to be in order, and such actions are hereby solicited. If any points remain in issue which the Examiner feels may be best resolved through a personal or telephone interview, the Examiner is kindly requested to contact the undersigned at the telephone number listed below.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,



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CUSTOMER NUMBER

Date: February 17, 2009